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The third column is the impact factor (IF) of the journal, and the fourth column is the number of citations of the article.

223 papers	6,726 citations	48 h-index	73 g-index
241 ext. papers	7,198 ext. citations	3.5 avg, IF	5.42 L-index

#	Paper	IF	Citations
223	Atomic layer deposition of oxide thin films with metal alkoxides as oxygen sources. <i>Science</i> , 2000 , 288, 319-21	33.3	415
222	Atomic Layer Deposition of Platinum Thin Films. <i>Chemistry of Materials</i> , 2003 , 15, 1924-1928	9.6	329
221	Effect of water dose on the atomic layer deposition rate of oxide thin films. <i>Thin Solid Films</i> , 2000 , 368, 1-7	2.2	227
220	Atomic Layer Deposition of Photocatalytic TiO ₂ Thin Films from Titanium Tetramethoxide and Water. <i>Chemical Vapor Deposition</i> , 2004 , 10, 143-148		190
219	Atomic Layer Deposition of Hafnium Dioxide Films from Hafnium Tetrakis(ethylmethanamide) and Water. <i>Chemical Vapor Deposition</i> , 2002 , 8, 199-204		174
218	Detection efficiency of time-of-flight energy elastic recoil detection analysis systems. <i>Nuclear Instruments & Methods in Physics Research B</i> , 1999 , 149, 477-489	1.2	134
217	Aluminum oxide from trimethylaluminum and water by atomic layer deposition: The temperature dependence of residual stress, elastic modulus, hardness and adhesion. <i>Thin Solid Films</i> , 2014 , 552, 124-135	2.2	119
216	Comparison of hafnium oxide films grown by atomic layer deposition from iodide and chloride precursors. <i>Thin Solid Films</i> , 2002 , 416, 72-79	2.2	114
215	Atomic layer deposition of polyimide thin films. <i>Journal of Materials Chemistry</i> , 2007 , 17, 664-669		111
214	Short-ranged structural rearrangement and enhancement of mechanical properties of organosilicate glasses induced by ultraviolet radiation. <i>Journal of Applied Physics</i> , 2006 , 99, 053511	2.5	109
213	Atomic Layer Deposition of SrTiO ₃ Thin Films from a Novel Strontium Precursor Strontium-bis(tri-isopropyl cyclopentadienyl). <i>Chemical Vapor Deposition</i> , 2001 , 7, 75-80		96
212	Properties of AlN grown by plasma enhanced atomic layer deposition. <i>Applied Surface Science</i> , 2011 , 257, 7827-7830	6.7	91
211	Plasma-Enhanced Atomic Layer Deposition of Silver Thin Films. <i>Chemistry of Materials</i> , 2011 , 23, 2901-2906	9.6	89
210	Potku New analysis software for heavy ion elastic recoil detection analysis. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2014 , 331, 34-41	1.2	88
209	Low-Temperature ALE Deposition of Y ₂ O ₃ Thin Films from Diketonate Precursors. <i>Chemical Vapor Deposition</i> , 2001 , 7, 44-50		87
208	Overview of material re-deposition and fuel retention studies at JET with the Gas Box divertor. <i>Nuclear Fusion</i> , 2006 , 46, 350-366	3.3	85
207	Surface-controlled growth of LaAlO ₃ thin films by atomic layer epitaxy. <i>Journal of Materials Chemistry</i> , 2001 , 11, 2340-2345		82

206	Low-temperature atomic layer deposition of ZnO thin films: Control of crystallinity and orientation. <i>Thin Solid Films</i> , 2011 , 519, 5319-5322	2.2	81
205	Atomic layer deposition of lithium containing thin films. <i>Journal of Materials Chemistry</i> , 2009 , 19, 8767		75
204	Gadolinium oxide thin films by atomic layer deposition. <i>Journal of Crystal Growth</i> , 2005 , 285, 191-200	1.6	67
203	Low Temperature Growth of High Purity, Low Resistivity Copper Films by Atomic Layer Deposition. <i>Chemistry of Materials</i> , 2011 , 23, 4417-4419	9.6	66
202	Atomic layer deposition of hafnium dioxide thin films from hafnium tetrakis(dimethylamide) and water. <i>Thin Solid Films</i> , 2005 , 491, 328-338	2.2	66
201	Analysis of ALD-processed thin films by ion-beam techniques. <i>Analytical and Bioanalytical Chemistry</i> , 2005 , 382, 1791-9	4.4	66
200	Atomic layer deposition and characterization of biocompatible hydroxyapatite thin films. <i>Thin Solid Films</i> , 2009 , 517, 5819-5824	2.2	64
199	ZrO ₂ Thin Films Grown on Silicon Substrates by Atomic Layer Deposition with Cp ₂ Zr(CH ₃) ₂ and Water as Precursors. <i>Chemical Vapor Deposition</i> , 2003 , 9, 207-212		63
198	Atomic layer deposition of rare earth oxides: erbium oxide thin films from βdiketonate and ozone precursors. <i>Journal of Alloys and Compounds</i> , 2004 , 374, 124-128	5.7	62
197	Monte Carlo simulation of multiple and plural scattering in elastic recoil detection. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2001 , 174, 163-172	1.2	62
196	Enhanced growth rate in atomic layer epitaxy deposition of magnesium oxide thin films. <i>Journal of Materials Chemistry</i> , 2000 , 10, 1857-1861		60
195	Low-Temperature Atomic Layer Deposition of Crystalline and Photoactive Ultrathin Hematite Films for Solar Water Splitting. <i>ACS Nano</i> , 2015 , 9, 11775-83	16.7	59
194	Time-of-flight Energy spectrometer for elemental depth profiling Design. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2014 , 337, 55-61	1.2	59
193	Atomic Layer Deposition of Spinel Lithium Manganese Oxide by Film-Body-Controlled Lithium Incorporation for Thin-Film Lithium-Ion Batteries. <i>Journal of Physical Chemistry C</i> , 2014 , 118, 1258-1268	3.8	58
192	Studies on atomic layer deposition of MOF-5 thin films. <i>Microporous and Mesoporous Materials</i> , 2013 , 182, 147-154	5.3	58
191	Effect of selected atomic layer deposition parameters on the structure and dielectric properties of hafnium oxide films. <i>Journal of Applied Physics</i> , 2004 , 96, 5298-5307	2.5	58
190	Surface-Controlled Deposition of Sc ₂ O ₃ Thin Films by Atomic Layer Epitaxy Using βDiketonate and Organometallic Precursors. <i>Chemistry of Materials</i> , 2001 , 13, 4701-4707	9.6	58
189	Review Article: Recommended reading list of early publications on atomic layer deposition Outcome of the Virtual Project on the History of ALD <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2017 , 35, 010801	2.9	55

188	Controlled growth of HfO ₂ thin films by atomic layer deposition from cyclopentadienyl-type precursor and water. <i>Journal of Materials Chemistry</i> , 2005 , 15, 2271		55
187	Radical-Enhanced Atomic Layer Deposition of Metallic Copper Thin Films. <i>Journal of the Electrochemical Society</i> , 2005 , 152, G25	3.9	54
186	Reduction of Copper Oxide Film to Elemental Copper. <i>Journal of the Electrochemical Society</i> , 2005 , 152, G122	3.9	54
185	Properties of hafnium oxide films grown by atomic layer deposition from hafnium tetraiodide and oxygen. <i>Journal of Applied Physics</i> , 2002 , 92, 5698-5703	2.5	54
184	One-Step Electrodeposition of Cu ₂ Se and CuInSe ₂ Thin Films by the Induced Co-deposition Mechanism. <i>Journal of the Electrochemical Society</i> , 2000 , 147, 1080	3.9	52
183	Atomic layer deposition of ferroelectric LiNbO ₃ . <i>Journal of Materials Chemistry C</i> , 2013 , 1, 4283-4290	7.1	51
182	Corrosion Protection of Steel with Oxide Nanolaminates Grown by Atomic Layer Deposition. <i>Journal of the Electrochemical Society</i> , 2011 , 158, C369	3.9	51
181	Atomic Layer Deposition and Properties of Lanthanum Oxide and Lanthanum-Aluminum Oxide Films. <i>Chemical Vapor Deposition</i> , 2006 , 12, 158-164		51
180	Thermal and plasma enhanced atomic layer deposition of SiO ₂ using commercial silicon precursors. <i>Thin Solid Films</i> , 2014 , 558, 93-98	2.2	50
179	Evidence of quantum phase slip effect in titanium nanowires. <i>Physical Review B</i> , 2012 , 85,	3.3	50
178	Evaluation of a Praseodymium Precursor for Atomic Layer Deposition of Oxide Dielectric Films. <i>Chemistry of Materials</i> , 2004 , 16, 5162-5168	9.6	50
177	Atomic Layer Deposition of Titanium Oxide from TiI ₄ and H ₂ O ₂ . <i>Chemical Vapor Deposition</i> , 2000 , 6, 303-310		50
176	Studies of impurity deposition/implantation in JET divertor tiles using SIMS and ion beam techniques. <i>Fusion Engineering and Design</i> , 2003 , 66-68, 219-224	1.7	49
175	Atomic Layer Deposition of Ruthenium Films from (Ethylcyclopentadienyl)(pyrrolyl)ruthenium and Oxygen. <i>Journal of the Electrochemical Society</i> , 2011 , 158, D158	3.9	48
174	Atomic Layer Deposition of Ta(Al)N(C) Thin Films Using Trimethylaluminum as a Reducing Agent. <i>Journal of the Electrochemical Society</i> , 2001 , 148, G566	3.9	48
173	Atomic layer deposition of Li _x Ti _y O _z thin films. <i>RSC Advances</i> , 2013 , 3, 7537-7542	3.7	46
172	Atomic Layer Deposition of Hafnium Dioxide Films from 1-Methoxy-2-methyl-2-propanolate Complex of Hafnium. <i>Chemistry of Materials</i> , 2003 , 15, 1722-1727	9.6	46
171	Deposition of yttria-stabilized zirconia thin films by atomic layer epitaxy from Ediketonate and organometallic precursors. <i>Journal of Materials Chemistry</i> , 2002 , 12, 442-448		46

170	Controlling the crystallinity and roughness of atomic layer deposited titanium dioxide films. <i>Journal of Nanoscience and Nanotechnology</i> , 2011 , 11, 8101-7	1.3	45
169	Atomic Layer Deposition of WO ₃ Thin Films using W(CO) ₆ and O ₃ Precursors. <i>Chemical Vapor Deposition</i> , 2012 , 18, 245-248		44
168	Variation of lattice constant and cluster formation in GaAsBi. <i>Journal of Applied Physics</i> , 2013 , 114, 243504	4.5	44
167	Atomic Layer Deposition of Hafnium Dioxide Films Using Hafnium Bis(2-butanolate)bis(1-methoxy-2-methyl-2-propanolate) and Water. <i>Chemical Vapor Deposition</i> , 2003 , 9, 315-320		43
166	Generalized Noise Study of Solid-State Nanopores at Low Frequencies. <i>ACS Sensors</i> , 2017 , 2, 300-307	9.2	42
165	Antibacterial and barrier properties of oriented polymer films with ZnO thin films applied with atomic layer deposition at low temperatures. <i>Thin Solid Films</i> , 2014 , 562, 331-337	2.2	42
164	Evaluation and Comparison of Novel Precursors for Atomic Layer Deposition of Nb ₂ O ₅ Thin Films. <i>Chemistry of Materials</i> , 2012 , 24, 975-980	9.6	41
163	Iridium metal and iridium oxide thin films grown by atomic layer deposition at low temperatures. <i>Journal of Materials Chemistry</i> , 2011 , 21, 16488		39
162	Low temperature atomic layer deposition of noble metals using ozone and molecular hydrogen as reactants. <i>Thin Solid Films</i> , 2013 , 531, 243-250	2.2	38
161	Atomic layer deposition of Al ₂ O ₃ , ZrO ₂ , Ta ₂ O ₅ , and Nb ₂ O ₅ based nanolayered dielectrics. <i>Journal of Non-Crystalline Solids</i> , 2002 , 303, 35-39	3.9	38
160	X-Ray absorption studies of cubic boron-carbon-nitrogen films grown by ion beam assisted evaporation. <i>Diamond and Related Materials</i> , 2001 , 10, 1165-1169	3.5	38
159	Linear Energy Transfer of Heavy Ions in Silicon. <i>IEEE Transactions on Nuclear Science</i> , 2007 , 54, 1158-1162	4.7	34
158	Tert-butylamine and Allylamine as Reductive Nitrogen Sources in Atomic Layer Deposition of TaN Thin Films. <i>Journal of Materials Research</i> , 2002 , 17, 107-114	2.5	34
157	Stabilizing organic photocathodes by low-temperature atomic layer deposition of TiO ₂ . <i>Sustainable Energy and Fuels</i> , 2017 , 1, 1915-1920	5.8	33
156	Atomic Layer Deposition of Osmium. <i>Chemistry of Materials</i> , 2012 , 24, 55-60	9.6	33
155	Atomic Layer Deposition of LiF Thin Films from Lithd, Mg(thd) ₂ , and TiF ₄ Precursors. <i>Chemistry of Materials</i> , 2013 , 25, 1656-1663	9.6	33
154	Low-energy heavy-ion TOF-ERDA setup for quantitative depth profiling of thin films. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2008 , 266, 5144-5150	1.2	33
153	HfO ₂ Films Grown by ALD Using Cyclopentadienyl-Type Precursors and H ₂ O or O ₃ as Oxygen Source. <i>Journal of the Electrochemical Society</i> , 2006 , 153, F39	3.9	33

152	Self-starting stretched-pulse fiber laser mode locked and stabilized with slow and fast semiconductor saturable absorbers. <i>Optics Letters</i> , 2001 , 26, 1809-11	3	32
151	Hardening Mechanisms in Graphitic Carbon Nitride Films Grown with N ₂ /Ar Ion Assistance. <i>Chemistry of Materials</i> , 2001 , 13, 129-135	9.6	32
150	Influence of thickness and growth temperature on the properties of zirconium oxide films grown by atomic layer deposition on silicon. <i>Thin Solid Films</i> , 2002 , 410, 53-60	2.2	31
149	Atomic Layer Deposition of SrS and BaS Thin Films Using Cyclopentadienyl Precursors. <i>Chemistry of Materials</i> , 2002 , 14, 1937-1944	9.6	31
148	Control of Oxygen Nonstoichiometry and Magnetic Property of MnCo ₂ O ₄ Thin Films Grown by Atomic Layer Deposition. <i>Chemistry of Materials</i> , 2010 , 22, 6297-6300	9.6	30
147	The production of the new cubic FeN phase by reactive magnetron sputtering. <i>Applied Surface Science</i> , 1999 , 138-139, 261-265	6.7	30
146	Atomic layer deposition of calcium oxide and calcium hafnium oxide films using calcium cyclopentadienyl precursor. <i>Thin Solid Films</i> , 2006 , 500, 322-329	2.2	29
145	Atomic layer deposition of HfO ₂ thin films and nanolayered HfO ₂ /Al ₂ O ₃ /Nb ₂ O ₅ dielectrics. <i>Journal of Materials Science: Materials in Electronics</i> , 2003 , 14, 361-367	2.1	29
144	Aluminum oxide/titanium dioxide nanolaminates grown by atomic layer deposition: Growth and mechanical properties. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2017 , 35, 01B105	2.9	28
143	Influence of plasma chemistry on impurity incorporation in AlN prepared by plasma enhanced atomic layer deposition. <i>Journal Physics D: Applied Physics</i> , 2013 , 46, 505502	3	27
142	Atomic Layer Deposition of High-Permittivity Yttrium-Doped HfO ₂ Films. <i>Electrochemical and Solid-State Letters</i> , 2009 , 12, G1		27
141	Evaluation of New Aminoalkoxide Precursors for Atomic Layer Deposition. Growth of Zirconium Dioxide Thin Films and Reaction Mechanism Studies. <i>Chemistry of Materials</i> , 2004 , 16, 5630-5636	9.6	27
140	Atomic Layer Deposition of Strontium Tantalate Thin Films from Bimetallic Precursors and Water. <i>Journal of the Electrochemical Society</i> , 2004 , 151, F69	3.9	26
139	Atomic Layer Deposition of Hafnium Dioxide Films from Hafnium Hydroxylamide and Water. <i>Chemical Vapor Deposition</i> , 2004 , 10, 91-96		25
138	Atomic layer deposition of Ru films from bis(2,5-dimethylpyrrolyl)ruthenium and oxygen. <i>Thin Solid Films</i> , 2012 , 520, 2756-2763	2.2	24
137	Nucleation and growth of ZnO on PMMA by low-temperature atomic layer deposition. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2015 , 33, 01A128	2.9	24
136	Programmable proximity aperture lithography with MeV ion beams. <i>Journal of Vacuum Science & Technology B</i> , 2008 , 26, 1732		24
135	Atomic Layer Deposition of Titanium Nitride Thin Films Using tert-Butylamine and Allylamine as Reductive Nitrogen Sources. <i>Electrochemical and Solid-State Letters</i> , 2002 , 5, C4		24

134	Properties of Oxide Film Atomic Layer Deposited from Tetraethoxy Silane, Hafnium Halides, and Water. <i>Journal of the Electrochemical Society</i> , 2004 , 151, F98	3.9	23
133	Broadband semiconductor saturable absorber mirrors in the 1.55- μm wavelength range for pulse generation in fiber lasers. <i>IEEE Journal of Quantum Electronics</i> , 2002 , 38, 369-374	2	22
132	Round Robin: measurement of H implantation distributions in Si by elastic recoil detection. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2004 , 222, 547-566	1.2	21
131	Structural and chemical analysis of annealed plasma-enhanced atomic layer deposition aluminum nitride films. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2016 , 34, 041506	2.9	20
130	High quality superconducting titanium nitride thin film growth using infrared pulsed laser deposition. <i>Superconductor Science and Technology</i> , 2018 , 31, 055017	3.1	19
129	Effects of surface roughness on results in elastic recoil detection measurements. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2000 , 161-163, 235-239	1.2	18
128	Effect of ozone concentration on silicon surface passivation by atomic layer deposited Al_2O_3 . <i>Applied Surface Science</i> , 2015 , 357, 2402-2407	6.7	17
127	Atomic layer deposited lithium aluminum oxide: (In)dependency of film properties from pulsing sequence. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2015 , 33, 01A101	2.9	17
126	Studies on atomic layer deposition of IRMOF-8 thin films. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2015 , 33, 01A121	2.9	17
125	Fabrication of microfluidic devices using MeV ion beam Programmable Proximity Aperture Lithography (PPAL). <i>Nuclear Instruments & Methods in Physics Research B</i> , 2008 , 266, 2461-2465	1.2	17
124	Hafnium tetraiodide and oxygen as precursors for atomic layer deposition of hafnium oxide thin films. <i>Thin Solid Films</i> , 2002 , 418, 69-72	2.2	17
123	Broadband Ultrahigh-Resolution Spectroscopy of Particle-Induced X Rays: Extending the Limits of Nondestructive Analysis. <i>Physical Review Applied</i> , 2016 , 6,	4.3	17
122	Atomic layer deposition of AlN from AlCl_3 using NH_3 and Ar/ NH_3 plasma. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2018 , 36, 021508	2.9	15
121	Characterization and Electrochemical Properties of Oxygenated Amorphous Carbon (a-C) Films. <i>Electrochimica Acta</i> , 2016 , 220, 137-145	6.7	15
120	Lithography exposure characteristics of poly(methyl methacrylate) (PMMA) for carbon, helium and hydrogen ions. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2012 , 272, 162-164	1.2	15
119	Investigation of $\text{ZrO}_2/\text{HfO}_2$ Based High-k Materials as Capacitor Dielectrics. <i>Journal of the Electrochemical Society</i> , 2010 , 157, G202	3.9	15
118	Development of an MeV ion beam lithography system in Jyväskylä. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2007 , 260, 77-80	1.2	15
117	Experimental Linear Energy Transfer of Heavy Ions in Silicon for RADEF Cocktail Species. <i>IEEE Transactions on Nuclear Science</i> , 2009 , 56, 2242-2246	1.7	14

116	Growth of osteoblasts on lithographically modified surfaces. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2007 , 260, 130-135	1.2	14
115	Effect of preparation conditions on properties of atomic layer deposited TiO ₂ films in MoO ₃ /TiO ₂ /Al stacks. <i>Thin Solid Films</i> , 2006 , 510, 39-47	2.2	14
114	Hafnium silicon oxide films prepared by atomic layer deposition. <i>Materials Science and Engineering B: Solid-State Materials for Advanced Technology</i> , 2004 , 109, 2-5	3.1	14
113	Thermal atomic layer deposition of AlO _x N _y thin films for surface passivation of nano-textured flexible silicon. <i>Solar Energy Materials and Solar Cells</i> , 2019 , 193, 231-236	6.4	13
112	Energy-loss straggling of 200 MeV/u Kr ions in gases. <i>European Physical Journal D</i> , 2013 , 67, 1	1.3	13
111	Transition-Edge Sensors for Particle Induced X-ray Emission Measurements. <i>Journal of Low Temperature Physics</i> , 2014 , 176, 285-290	1.3	13
110	Depth profiling of Al ₂ O ₃ +TiO ₂ nanolaminates by means of a time-of-flight energy spectrometer. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2011 , 269, 3021-3024	1.2	13
109	Atomic Layer Deposition and Characterization of Aluminum Silicate Thin Films for Optical Applications. <i>Journal of the Electrochemical Society</i> , 2011 , 158, P15	3.9	13
108	Room-temperature plasma-enhanced atomic layer deposition of ZnO: Film growth dependence on the PEALD reactor configuration. <i>Surface and Coatings Technology</i> , 2017 , 326, 281-290	4.4	12
107	Porous inorganic/organic hybrid material by oxygen plasma treatment. <i>Journal of Micromechanics and Microengineering</i> , 2011 , 21, 125003	2	12
106	Low friction ta-C films with hydrogen reservoirs. <i>Diamond and Related Materials</i> , 2001 , 10, 1030-1035	3.5	12
105	Blistering mechanisms of atomic-layer-deposited AlN and Al ₂ O ₃ films. <i>Applied Physics Letters</i> , 2017 , 111, 141606	3.4	11
104	Nanotribological, nanomechanical and interfacial characterization of atomic layer deposited TiO ₂ on a silicon substrate. <i>Wear</i> , 2015 , 342-343, 270-278	3.5	11
103	Plasma etch characteristics of aluminum nitride mask layers grown by low-temperature plasma enhanced atomic layer deposition in SF ₆ based plasmas. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2012 , 30, 011504	2.9	11
102	Wettability and compositional analysis of hydroxyapatite films modified by low and high energy ion irradiation. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2008 , 266, 2515-2519	1.2	11
101	ALD of Ta(Si)N Thin Films Using TDMAS as a Reducing Agent and as a Si Precursor. <i>Journal of the Electrochemical Society</i> , 2004 , 151, G523	3.9	11
100	Chemically guided epitaxy of Rb-irradiated α -quartz. <i>Journal of Applied Physics</i> , 2004 , 95, 4705-4713	2.5	11
99	Ozone-Based Atomic Layer Deposition of Al ₂ O ₃ from Dimethylaluminum Chloride and Its Impact on Silicon Surface Passivation. <i>Advanced Electronic Materials</i> , 2017 , 3, 1600491	6.4	10

98	Low-Temperature Molecular Layer Deposition Using Monofunctional Aromatic Precursors and Ozone-Based Ring-Opening Reactions. <i>Langmuir</i> , 2017 , 33, 9657-9665	4	10
97	Atomic Layer Deposition and Characterization of Erbium Oxide-Doped Zirconium Oxide Thin Films. <i>Journal of the Electrochemical Society</i> , 2010 , 157, G193	3.9	10
96	Depth resolution optimization for low-energy ERDA. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2007 , 261, 512-515	1.2	10
95	Epitaxial recrystallization of amorphized quartz after sodium ion implantation and oxygen annealing. <i>Surface and Coatings Technology</i> , 2002 , 158-159, 436-438	4.4	10
94	Excellent silicon surface passivation using dimethylaluminium chloride as Al source for atomic layer deposited Al ₂ O ₃ . <i>Physica Status Solidi (A) Applications and Materials Science</i> , 2015 , 212, 1795-1799	1.6	9
93	The analysis of a thin SiO ₂ /Si ₃ N ₄ /SiO ₂ stack: A comparative study of low-energy heavy ion elastic recoil detection, high-resolution Rutherford backscattering and secondary ion mass spectrometry. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2006 , 249, 847-850	1.2	9
92	Dynamics of photoluminescence in GaInNAs saturable absorber mirrors. <i>Applied Physics A: Materials Science and Processing</i> , 2003 , 77, 861-863	2.6	9
91	Ion beam mixing in Fe/Si and Ta/Si bilayers: Possible effects of ion charges. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2003 , 205, 741-745	1.2	9
90	Blue- and green-emitting SrS:Cu electroluminescent devices deposited by the atomic layer deposition technique. <i>Journal of Applied Physics</i> , 2003 , 94, 3862-3868	2.5	9
89	Normal-Metal/Insulator/Superconductor Tunnel Junction With Atomic-Layer-Deposited Titanium Nitride as Superconductor. <i>IEEE Transactions on Applied Superconductivity</i> , 2015 , 25, 1-4	1.8	8
88	Antiferromagnetism and p-type conductivity of nonstoichiometric nickel oxide thin films. <i>Information Materials</i> , 2020 , 2, 769-774	23.1	8
87	Low-temperature atomic layer deposition of SiO/AlO multilayer structures constructed on self-standing films of cellulose nanofibrils. <i>Philosophical Transactions Series A, Mathematical, Physical, and Engineering Sciences</i> , 2018 , 376,	3	8
86	Time-of-flight ERD with a 200 mm ² Si ₃ N ₄ window gas ionization chamber energy detector. <i>Nuclear Instruments & Methods in Physics Research B</i> , 2014 , 332, 271-274	1.2	8
85	Recent negative ion source activity at JYFL 2013 ,		8
84	The impact of the density and type of reactive sites on the characteristics of the atomic layer deposited WN _x Cy films. <i>Journal of Applied Physics</i> , 2006 , 99, 063515	2.5	8
83	Characterization of surface layers in Zn-diffused LiNbO ₃ waveguides by heavy ion elastic recoil detection. <i>Applied Physics Letters</i> , 2002 , 81, 1981-1983	3.4	8
82	Al ₂ O ₃ ALD films grown using TMA + rare isotope ² H ²¹⁶ O and ¹ H ²¹⁸ O precursors. <i>Applied Surface Science</i> , 2021 , 546, 148909	6.7	8
81	Nanoscale etching of III-V semiconductors in acidic hydrogen peroxide solution: GaAs and InP, a striking contrast in surface chemistry. <i>Applied Surface Science</i> , 2019 , 465, 596-606	6.7	8

80	Tribological properties of thin films made by atomic layer deposition sliding against silicon. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2018 , 36, 01A122	2.9	7
79	Comparison of mechanical properties and composition of magnetron sputter and plasma enhanced atomic layer deposition aluminum nitride films. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2018 , 36, 051508	2.9	7
78	Structural and Optical Characterization of ZnS Ultrathin Films Prepared by Low-Temperature ALD from Diethylzinc and 1,5-Pentanedithiol after Various Annealing Treatments. <i>Materials</i> , 2019 , 12,	3.5	7
77	Aperture-edge scattering in MeV ion-beam lithography. II. Scattering from a rectangular aperture. <i>Journal of Vacuum Science & Technology B</i> , 2009 , 27, 1109		7
76	Effect of isotopic substitution on IR and ESR properties of mass selected ion beam deposited ta-C films. <i>Diamond and Related Materials</i> , 2003 , 12, 900-904	3.5	7
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